



**RESPONSE UNDER 37. C.F.R. § 1.116  
EXPEDITED PROCEDURE  
EXAMINING GROUP 1762**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In Re Patent Application of: )  
Janardhanan Anand Subramony, et al. ) Examiner: Meeks, Timothy H.  
Application No.: 10/041,026 ) Art Unit: 1762  
Filed: December 28, 2001 ) Confirmation No. 2626  
For: METHOD FOR SILICON OXIDE AND )  
OXYNITRIDE DEPOSITION USING )  
SINGLE WAFER LOW PRESSURE CVD )  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**AMENDMENT AND RESPONSE TO OFFICE ACTION**

Dear Sir:

In response to the Final Office Action dated August 21, 2003, please enter this Amendment and consider the following remarks.

**FIRST CLASS CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage in an envelope addressed to the Commissioner for Patents, P.O. Box 1450 Alexandria, VA, 22313-1450

on September 26, 2003

Date of Deposit

Michelle Begay

Name of Person Mailing Correspondence

Michelle Begay

Signature

September 26, 2003

Date